

Title (en)
METHOD AND DEVICE FOR PRODUCING A PLASMA

Title (de)
VERFAHREN UND VORRICHTUNG ZUR ERZEUGUNG EINES PLASMAS

Title (fr)
PROCEDE ET DISPOSITIF DE GENERATION DE PLASMA

Publication
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Application
EP 02777222 A 20020926

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Abstract (en)
[origin: WO03030207A1] The invention relates to a method for producing a plasma. Said plasma is produced in the vacuum chamber (1a) of a vacuum recipient (1) of a device which is suitable for plasma treatment, by means of at least one induction coil (2) which is acted upon by an alternating current. The gas used to produce the plasma is introduced into the vacuum chamber (1a) via at least one inlet (3), and the vacuum chamber (1a) is pumped by means of at least one pumping unit (4). In order to influence the density of the plasma, the induction coil (2) is additionally acted upon by an optionally pulsed direct current.

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IPC 8 full level
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H01J 37/321 (2013.01 - EP US); **H01J 37/32174** (2013.01 - EP US); **H01J 37/3266** (2013.01 - EP US); **H01L 21/3065** (2013.01 - KR)

Citation (search report)
See references of WO 03030207A1

Citation (examination)
• JP H10284298 A 19981023 - MATSUSHITA ELECTRIC IND CO LTD
• WO 0137315 A1 20010525 - LAM RES CORP [US], et al

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